

204612US-2

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF:

YUUICHI HIRANO ET AL.

: EXAMINER: THIEN F. TRAN

SERIAL NO: 09/802,886

:

FILED: MARCH 12, 2001

: GROUP ART UNIT: 2811

FOR: SEMICONDUCTOR DEVICE AND

METHOD OF MANUFACTURING THE SAME

AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS WASHINGTON, D.C. 20231

SIR:

In response to the Office Action dated June 6, 2002, please enter the following Amendment and consider the following Remarks:

IN THE CLAIMS

Please amend the claims as shown in the Attachment, in which underlining and bracketing show the changes introduced into the previously-pending claims to arrive at the clean claims provided below:

1. (Amended) A semiconductor device comprising:

an SOI substrate having a structure in which a semiconductor substrate, an insulating layer and a semiconductor layer are layered in this order;

a partial-isolation insulating film formed in a main surface of said semiconductor layer.

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AUG 30 (2002